MEDIA ALERT

OCTOBER 12, 2009

D2S TO SPEAK AT THE INTERNATIONAL CONFERENCE ON COMPUTER-AIDED DESIGN

Tutorial to Further Educate Design Community on the Future of E-beam Direct Write Technologies

D2S, an emerging design and software company, today announced that Aki Fujimura, Chairman and CEO of the company, will provide a tutorial at the International Conference on Computer-Aided Design (ICCAD) on Monday, November 2, 2009 at the DoubleTree Hotel in San Jose, Calif. The talk will be held within the design for manufacturing (DFM) tutorial from 11:00 a.m. to 12:30 p.m. and discuss e-beam direct write (EbDW) and design for e-beam (DFEB).

As the industry moves to smaller geometries, mask costs become an even bigger challenge for IC manufacturers—making low-volume production of custom ICs economically infeasible. D2S's tutorial will provide the industry with alternative methods for low-volume, high-value designs. It will accomplish this by delving into the various maskless EbDW technologies in production today, as well as providing you with a glimpse into the roadmap for the future.

D2S' tutorial will be made available online after November 2 at www.direct2silicon.com.

About D2S
D2S is empowering an era of new business opportunities for electronic products by making low-volume silicon production cost effective at the 65-nanometer node and below. D2S' advanced design for-e-beam (DFEB) design and software capabilities maximize existing e-beam technology to virtually eliminate the costs of masks and can speed time to market by shortening the design-to-lithography process flow. Headquartered in San Jose, Calif., the company was founded in 2007. For more information, see: http://www.direct2silicon.com/.